

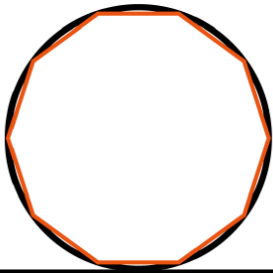
CLEO Europe EQEC 2019 (CK-5.6)

June 24, 15:30-15:45 2019

Precisely Dispersion Tailored Crystalline Microresonator with a Q Exceeding 10^8 Fabricated by Computer-controlled Machining

Shun Fujii¹, Mika Fuchida¹, Hikaru Amano², Shuya Tanaka¹,
Ryo Suzuki¹, Yasuhiro Kakinuma², and Takasumi Tanabe¹

1. Department of Electronics and Electrical Engineering,
Faculty of Science and Technology, Keio University
2. Department of System Design Engineering,
Faculty of Science and Technology, Keio University

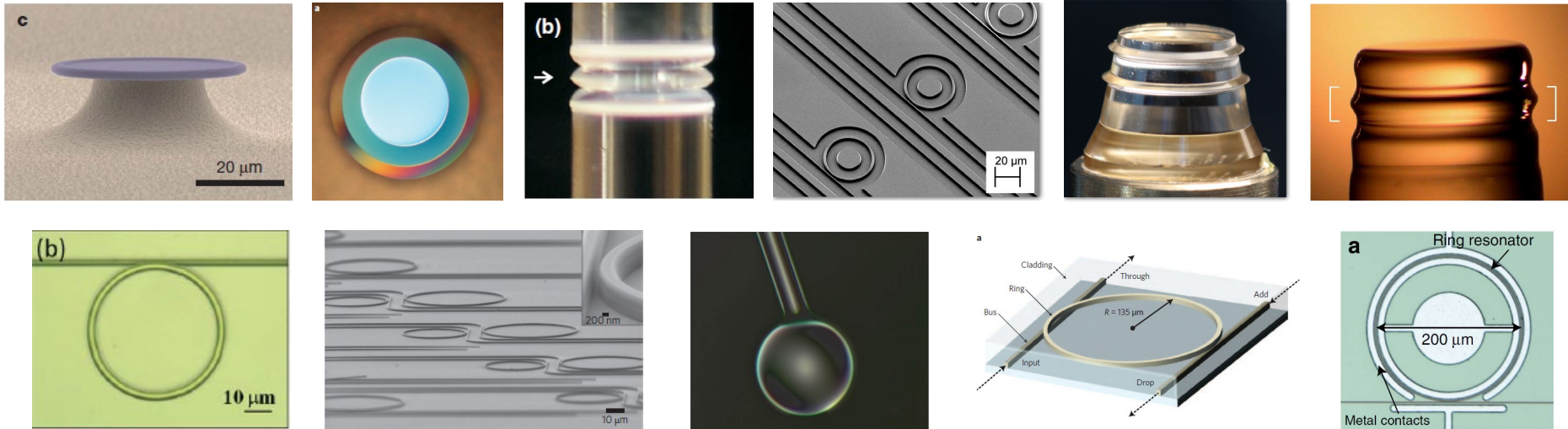


Whispering gallery mode (WGM) optical microresonator

Confines light for long photon lifetime (high Q) and has small volume

Enhances light-matter interaction in dielectric material

Dielectric microresonator platforms (Caltech, NIST, EPFL, OEwaves, Columbia, Harvard, Yale, INRS-EMT)



$$(\text{Intracavity power}) = \frac{4\eta d_1 Q}{\omega_0} \times (\text{Input power})$$

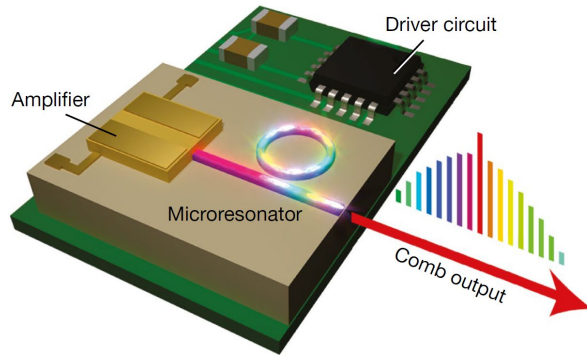
ω_0 : laser frequency, d_1 : cavity FSR,
 Q : quality factor, η : coupling parameter

e.g. $\omega_0/2\pi = 193$ THz, $d_1 = 100$ GHz,
 $Q = 1 \times 10^8$, $\eta = 0.5$ (critical coupling)

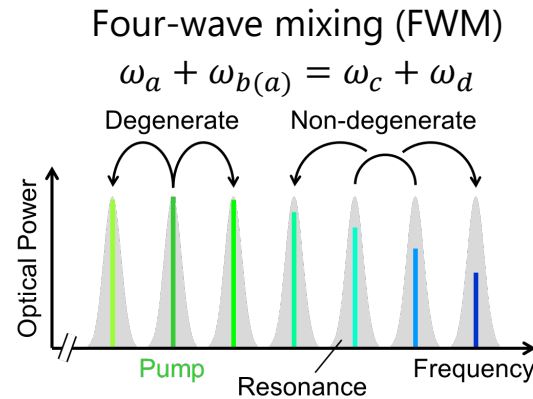
10 mW input \Rightarrow 165 W intracavity



Target application: Microresonator frequency comb (Kerr comb)



Nature 562, 401–405 (2018)



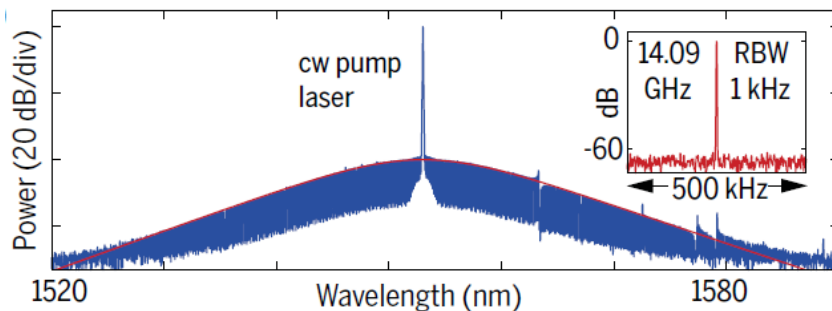
Threshold power for FWM

$$P_{\text{th}} = \frac{\kappa^2 n_0^2 V_{\text{eff}}}{8\eta\omega_0 c n_2} \propto \frac{V}{n_2 Q^2}$$

- Compact size
- Low energy consumption
- Broad bandwidth
- Large mode spacing ~ 1000 GHz

Optical spectrum of soliton

Science 361, 8083 (2018)

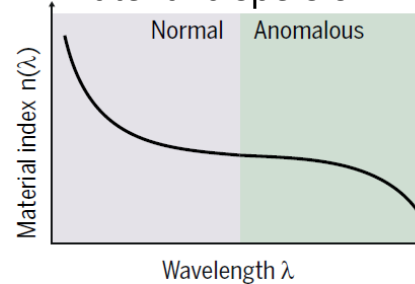


- Mode-locked state in Kerr comb (Kerr soliton)

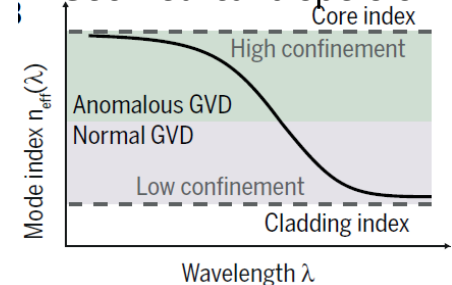
$$\Psi(\mu) = \sqrt{d_2/2} \operatorname{sech} \left(\frac{\pi\mu}{2} \sqrt{\frac{d_2}{\zeta_0}} \right) \quad \begin{aligned} d_2 &= D_2/\kappa \\ \zeta_0 &= \pi^2 f^2/8 \end{aligned}$$

Microresonator dispersion

Material dispersion



Geometrical dispersion



- Anomalous dispersion condition required

$$\beta_2 < 0 \quad (D_2 > 0) \quad \beta_2 = \frac{d^2\beta}{d\omega^2} = -\frac{nD_2}{cD_1^2}$$



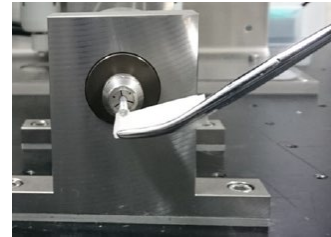
Mainstream microresonator fabrication methods



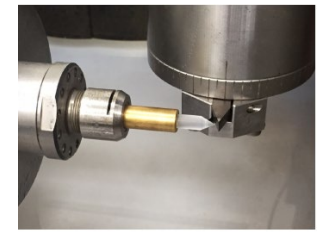
CO₂ laser reflow



Chemical etching



Polishing



Machining

Silica (SiO₂)
Toroid / Sphere / Rod

Q ~ 10⁸

Only amorphous
Geometric control ✗

Silica (SiO₂) disk
Silicon nitride (SiN)
Diamond Silicon (Si)

Q ~ 10⁷

Various materials
Geometric control ○

Fluoride crystal
MgF₂ CaF₂ BaF₂
LiNbO₃(PPLN)

Q ~ 10¹⁰

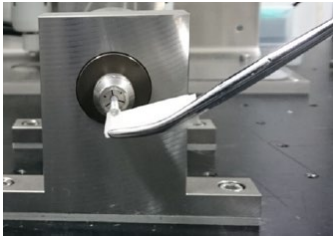
Ultra-high Q
Geometric control ✗

Q ~ 10⁶

Low Q
Geometric control ○



Combination of two methods



Polishing



Machining

Fluoride crystal

MgF_2 CaF_2 BaF_2

LiNbO_3 (PPLN)

$Q \sim 10^{10}$

$Q \sim 10^6$

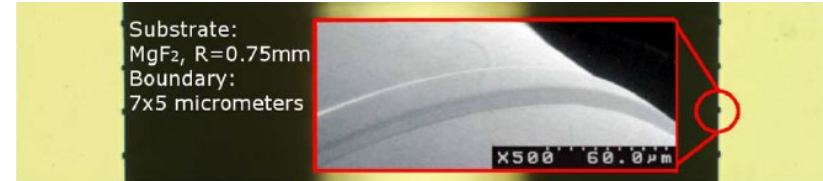
Ultra-high Q

Low Q

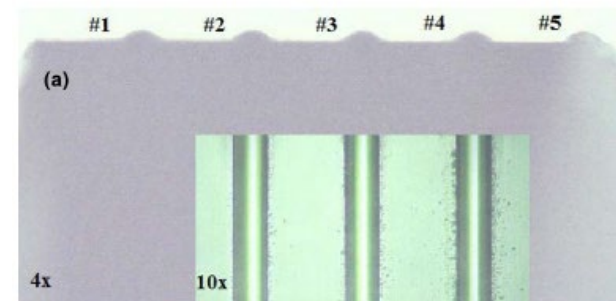
Form accuracy ✘

Form accuracy ○

Crystalline resonators formed by hand polishing after diamond turning process (Q exceeding 10^8)



Optica 2, 221 (2015)



Optics Letters 42, 514 (2017)

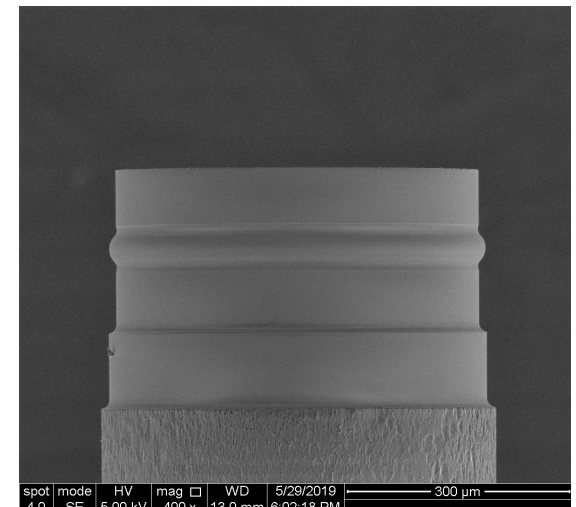
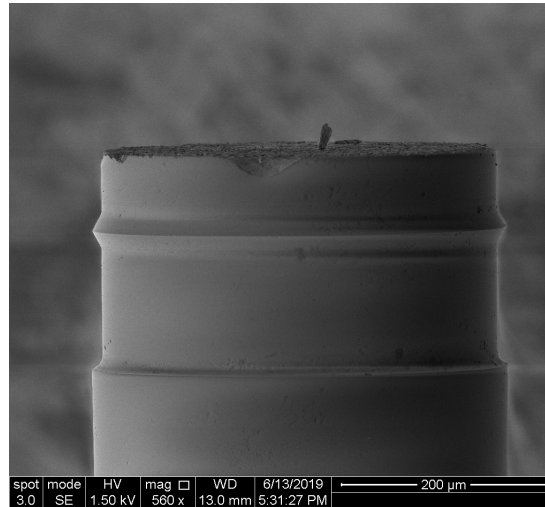
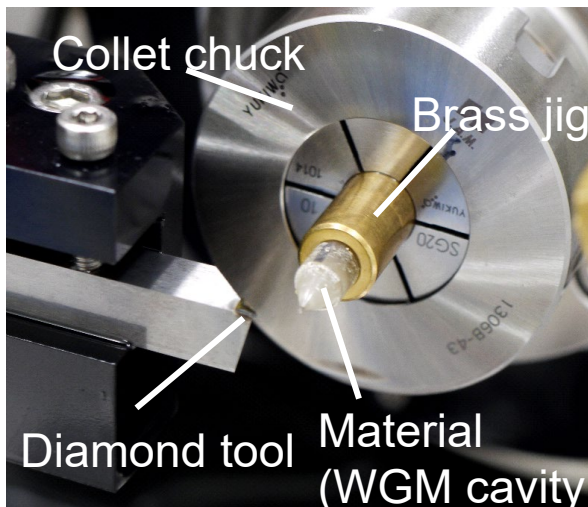
- Ultra-high Q ($Q > 10^9$) achieved by polishing after computer-controlled machining process
- Additional hand polishing degrades predesigned geometry (disadvantage for dispersion tailoring)
- Never again producing the standard microresonators



Motivation

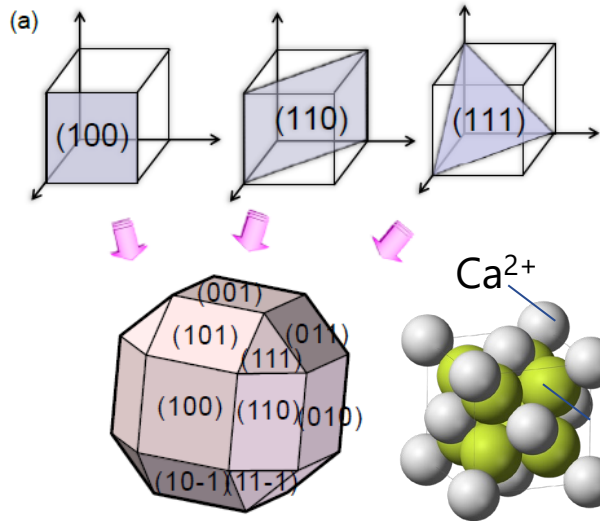
- Fabricate ultra-high Q crystalline microresonators ($Q > 10^8$) by computer-controlled machining **without polishing**
- Explore the potential of dispersion engineering for crystalline microresonators towards soliton formation at broadband wavelengths

Fully computer-controlled ultra-precision machining for dispersion engineering



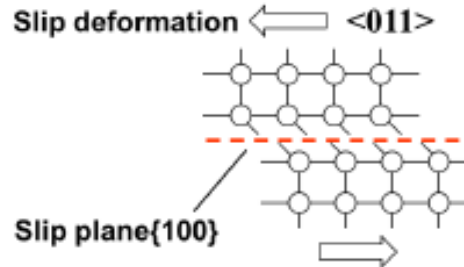


Crystallographic image of CaF_2 material

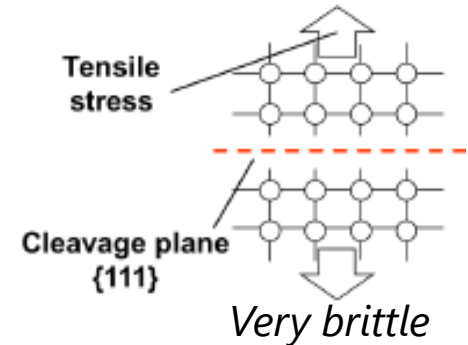


- Plane of single crystal is defined as mirror index
- CaF_2 consists of only 3 planes (100), (110), (111)
- Cutting mode transition observed with cutting depth

Slip formation (100)[110]

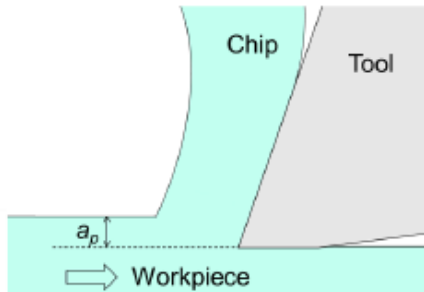


Cleavage formation (111)



Cutting mode transition is observed depending on crystal anisotropy

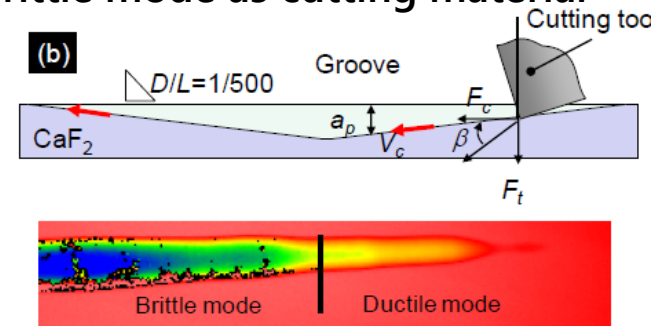
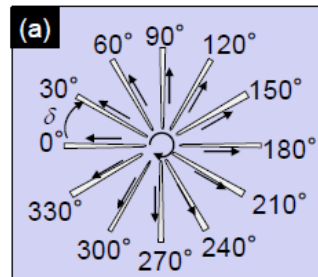
Ductile-mode cutting



Brittle-mode cutting



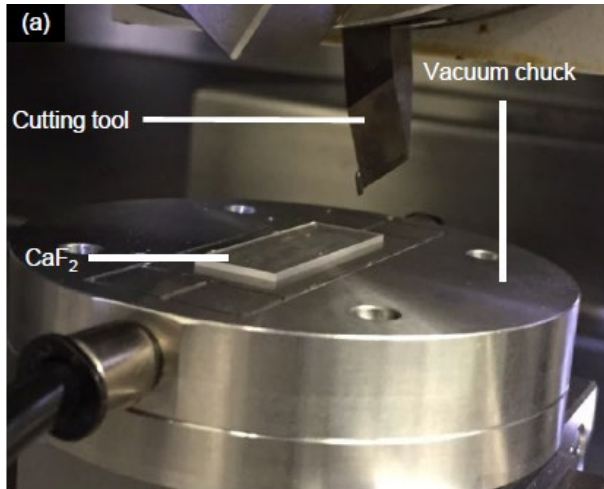
Transition to brittle mode as cutting material



Cutting depth < Critical depth Cutting depth > Critical depth



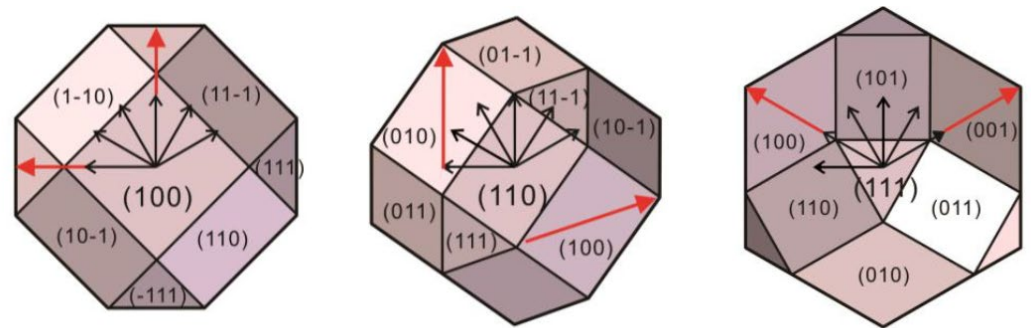
Experimental setup



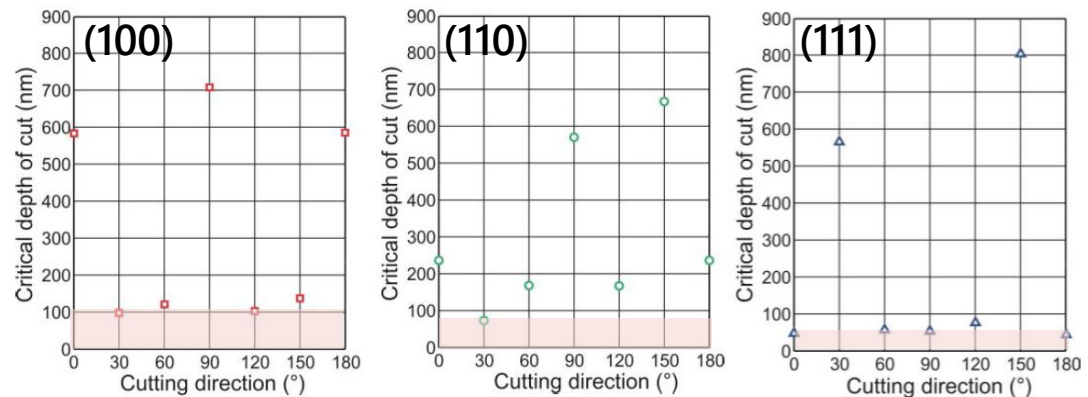
“Objective” of orthogonal cutting experiment

- Resonators must be fabricated with ductile-mode cutting
- Identify critical cutting depth for all crystal planes and cutting directions with orthogonal cutting experiment

Critical cutting depth vs direction for different planes

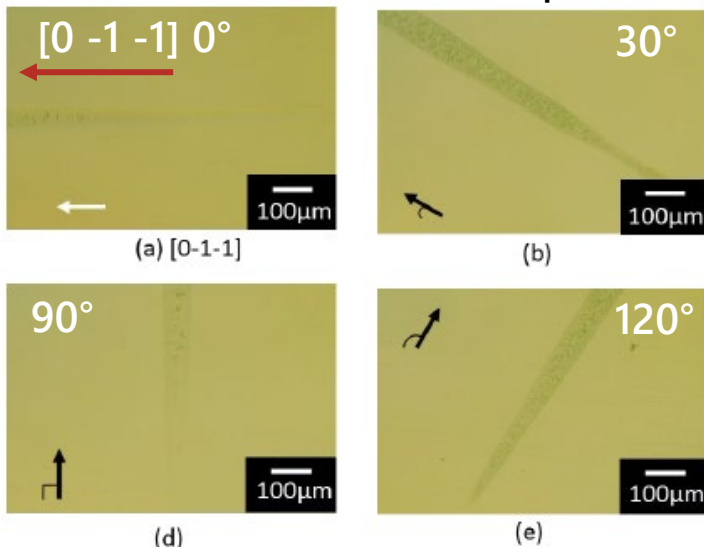


← Slip system ← Cutting direction



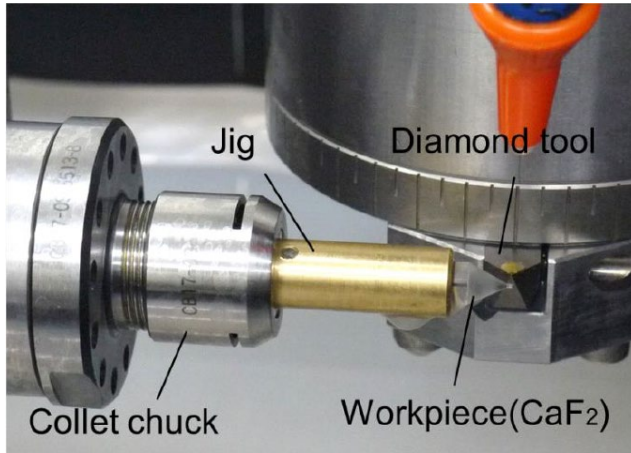
Critical cutting depth is over 50 nm for all planes

Machined surface of (100) plane



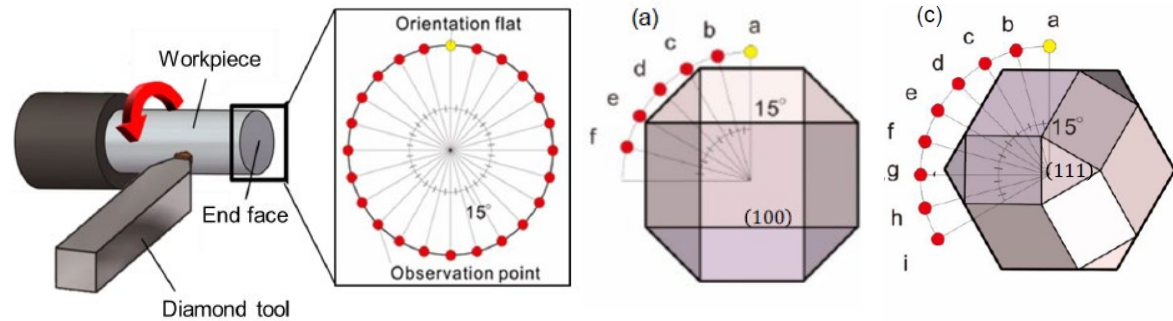


Experimental setup

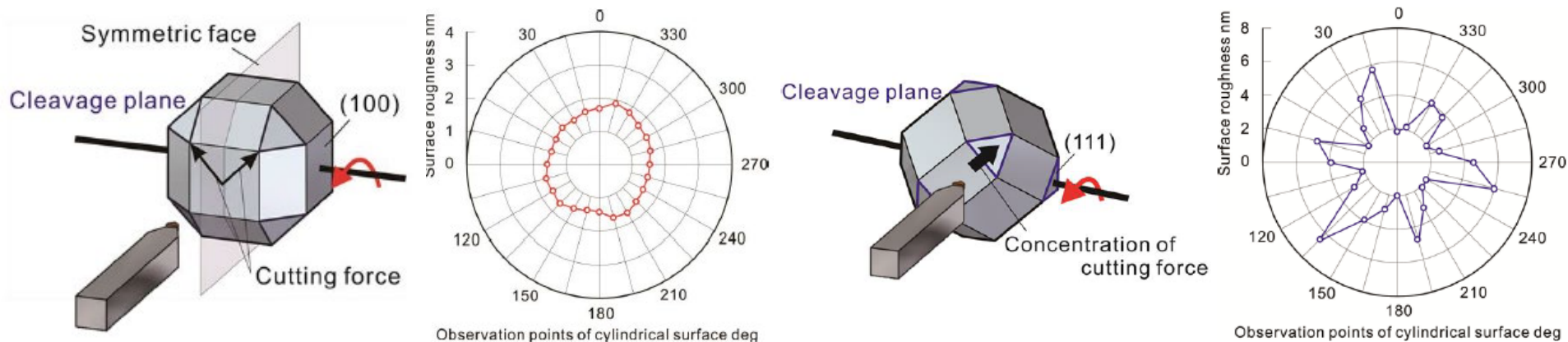


“Objective” of cylindrical turning experiment

- Cutting plane and direction are continuously and simultaneously changed when resonator is turned
- Investigate surface roughness of entire cylindrical surface



Cylindrical surface roughness for observation points with different end-faces

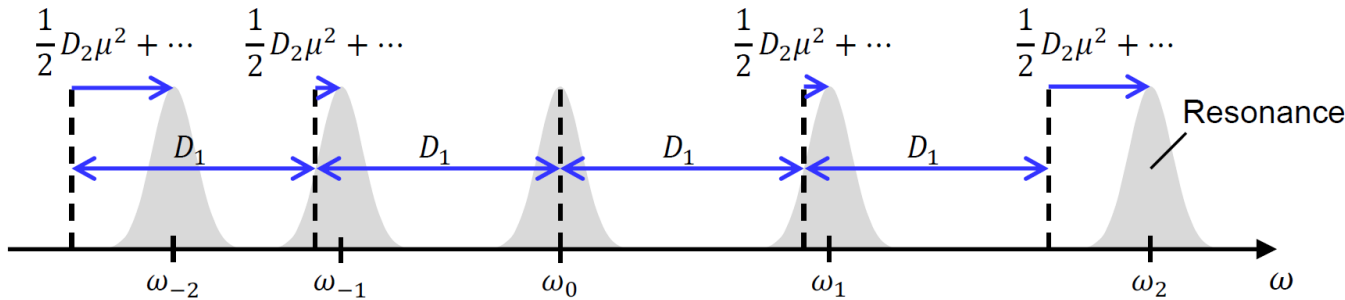
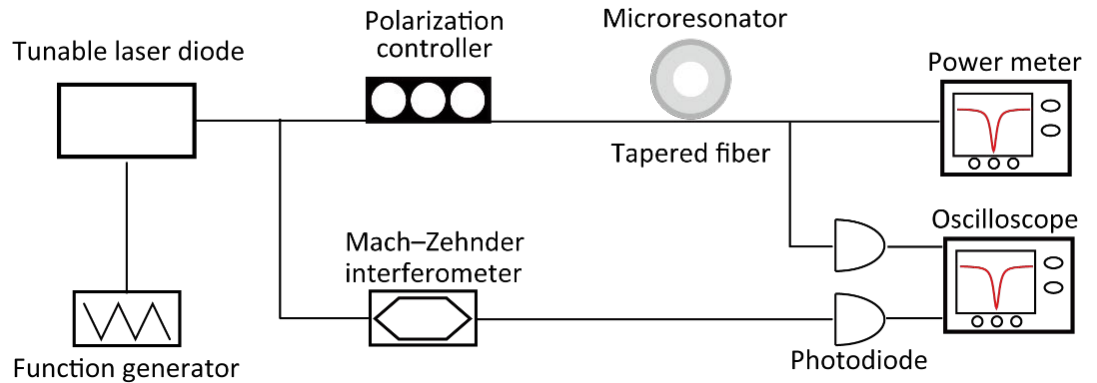
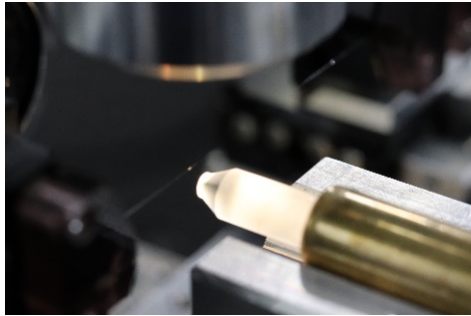


Observed smooth surface with end-face (100)

Observed surface clack with the end-face (111)



Experimental setup for Q-factor and dispersion measurement



Group-velocity dispersion

$D_2 > 0$: anomalous
 $D_2 < 0$: normal

Resonance frequency:
$$\omega_m = \frac{2\pi mc}{Ln(\omega)}$$

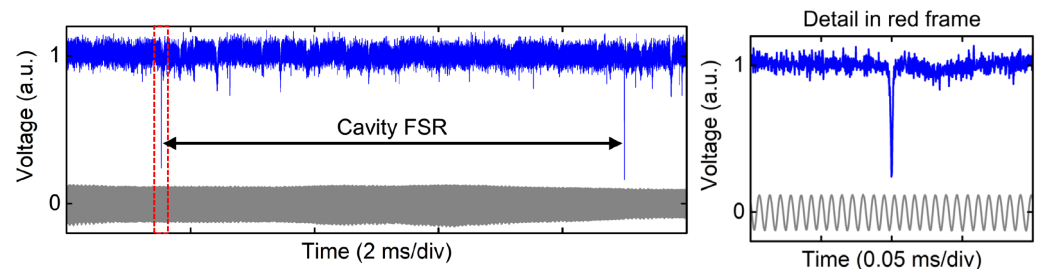
Resonance frequencies are Taylor-expanded:

$$\omega_\mu = \omega_0 + D_1\mu + \frac{1}{2}D_2\mu^2 + \frac{1}{6}D_3\mu^3 + \dots$$

m : mode number

μ : mode number offset (from pump $\mu = 0$)

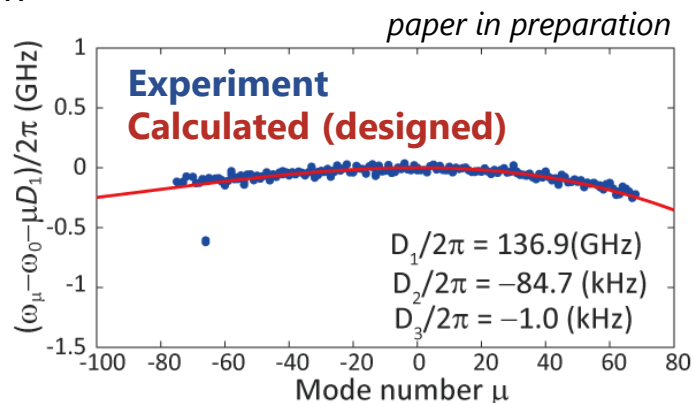
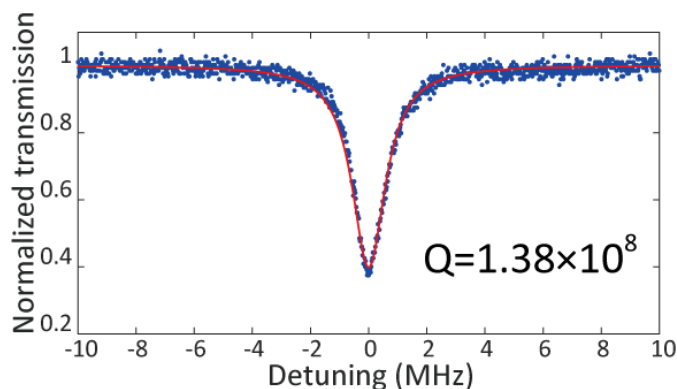
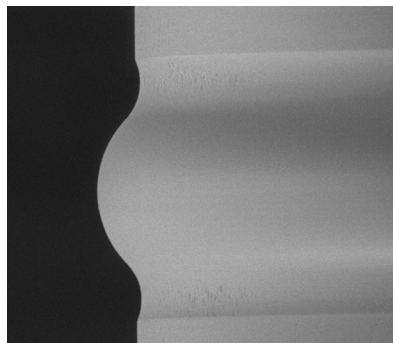
Mach-Zehnder interferometer calibrates frequency axis



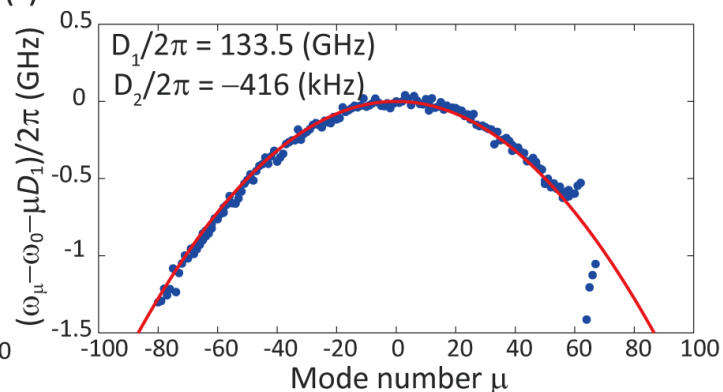
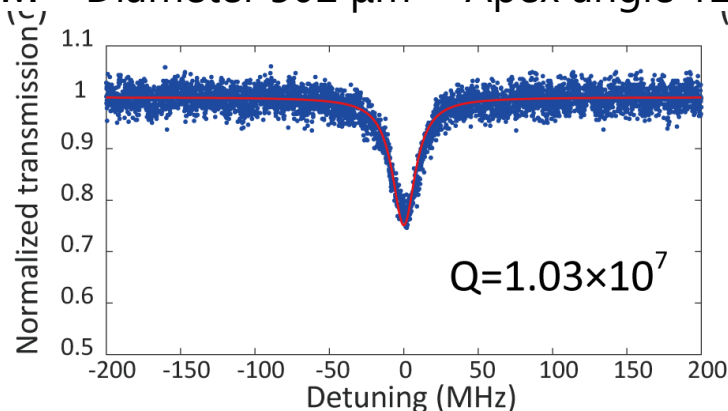
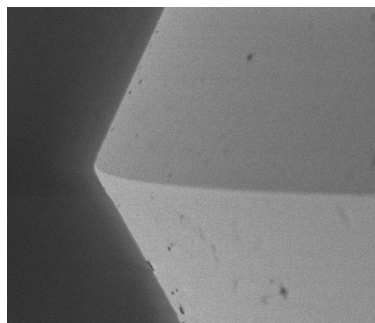


Crystalline microresonator fabricated "*without polishing*"

Spherical MgF_2 WGM Diameter 508 μm Curvature 36 μm



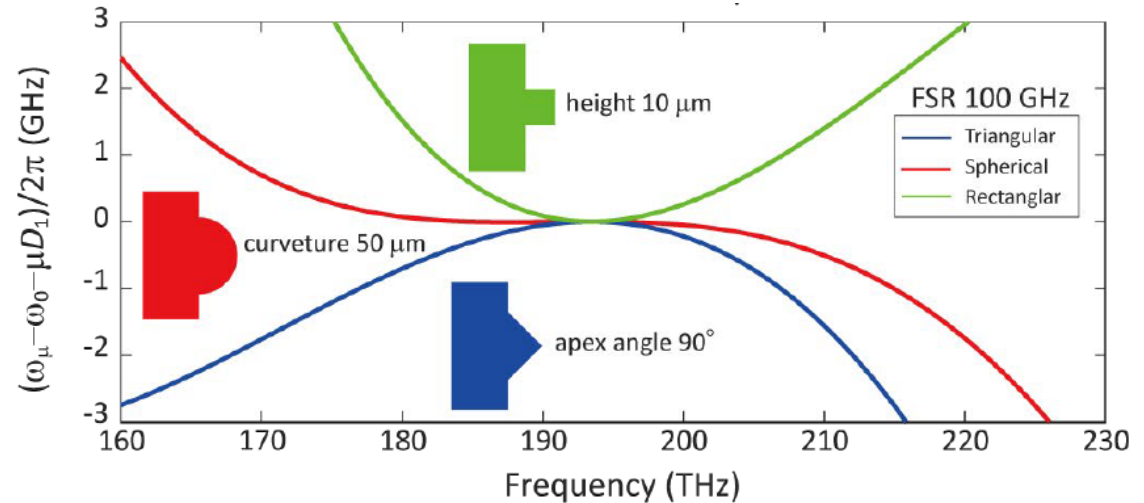
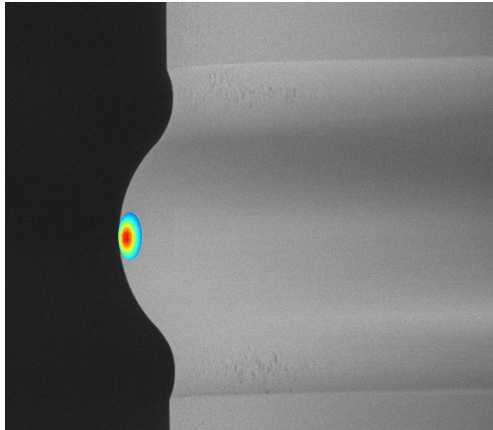
Triangular CaF_2 WGM Diameter 502 μm Apex angle 120°



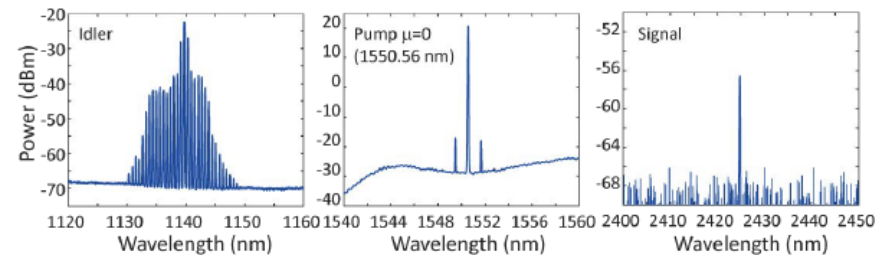
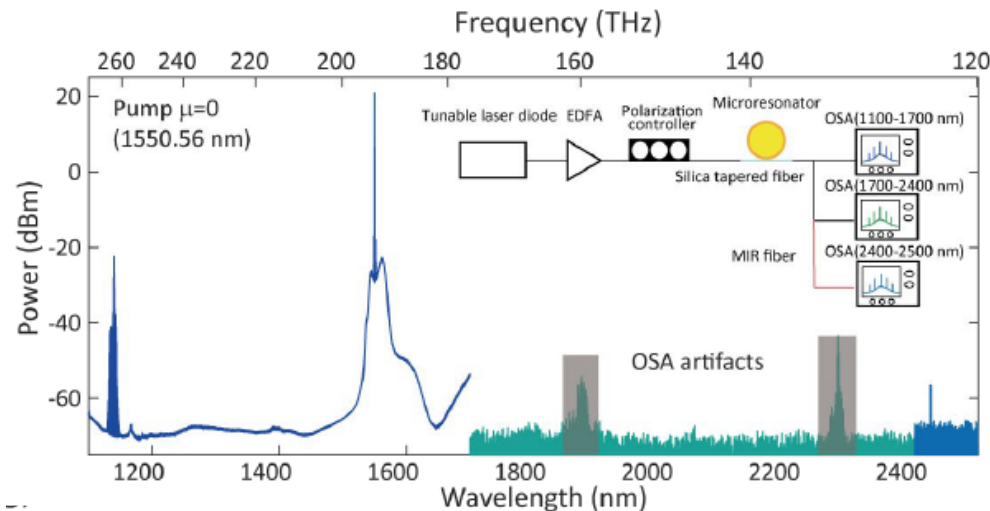
- Highest Q-factor exceeding 10^8 was observed in MgF_2 spherical WGM resonator
- Effect of crystal anisotropy and best end-face should be investigated
- MgF_2 is more suitable for Kerr comb generation as regards thermal stability



Simulated dispersion for different resonator structure with 100 GHz FSR



Phase-matched four-wave mixing (FWM) in dispersion engineered microresonator






- FWM sidebands spanning 1-octave
- Phase-matching via higher-order dispersion



- Identified critical depth and for each end-face orientation to achieve ultra-precision machining of CaF₂ WGM microresonators
- Observed highest Q exceeding 10⁸ and microcomb without polishing process
- Investigated ideal WGM structure for 100-GHz FSR microcomb generation

Summary of crystalline microresonators fabricated without polishing

	CaF ₂ Spherical WGM	Q = 7.67 × 10 ⁷	FSR = 129.8 GHz	D ₂ /2π = -267 kHz
		Q = 6.07 × 10 ⁷	FSR = 22.08 GHz	D ₂ /2π = -2.3 kHz
	CaF ₂ Triangular WGM	Q = 1.03 × 10 ⁷	FSR = 133.5 GHz	D ₂ /2π = -416 kHz
	MgF ₂ Spherical WGM	Q = 1.38 × 10 ⁸	FSR = 136.9 GHz	D ₂ /2π = -84.7 kHz
		Q = 2.1 × 10 ⁷	FSR = 21.61 GHz	D ₂ /2π = 4.86 kHz

Thank you

Acknowledgment

This work is supported by Japan Society for the Promotion of Science (JSPS) KAKENHI under Grant Number JP19H00873, JP18J21797 and Grant-in-Aid for JSPS Fellow; Amada Foundation; The Ministry of Education, Culture, Sports, Science and Technology (MEXT) Q-LEAP

We thank Dr. Y. Mizumoto, H. Kangawa, and Ms. Y. Hayama for their contribution of this work